Patent

Atty. Docket: H60-104 US

Certificate of Mailing

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Germaine Brenkert

Dated: March 5, 2002

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant

J. Ramm

Serial No.

10/002,996

Filing Date

October 25, 2001

Examiner

Unknown

Group Art Unit

Unknown

For

METHOD FOR PRODUCING COATED SUBSTRATES

Commissioner for Patents Washington, D.C. 20231

INFORMATION DISCLOSURE STATEMENT

Sir:

This Information Disclosure Statement is submitted:

- [] Under 37 C.F.R. 1.129(a), or (First/Second Submission after Final Rejection)
- [XX] Under 37 C.F.R. 1.97(b), or (Within any one of the following time periods: three (3) months of filing national application, other than a CPA, or date of entry of the national stage in an international application; or before the mailing date of a first official action on the merits in a non-provisional application, including a CPA; or a Request for Continued Examination (RCE)
- [] Under 37 C.F.R. 1.97(c), together with either:
 - [] Statement under 37 C.F.R. 1.97(e), as checked below, or
 - [] Fee of \$180.00 under 37 C.F.R. 1.17(p), or (After the 37 C.F.R. 1.97(b) time period, but before Final Office Action or Notice of Allowance, whichever issues first)
- Under 37 C.F.R. 1.97(d), together with:
 - [] Statement under 37 C.F.R. 1.97(e), as checked below, and
 - [] Fee of \$180.00 under 37 C.F.R. 1.17(p), or (Filed after Final Office Action or Notice of Allowance, whichever issues first, but on or before payment of Issue Fee)

[}		Under 37 C.F.R. 1.97 (i):
]	Applicant respectfully requests that the I.D.S. and cited reference(s) be placed in the application file wrapper (Filed after payment of Issue Fee).
Statement Under 37 C.F.R. 1.97(e):			
[3		Each item of information contained in this Information Disclosure Statement was first cited in any communication from a foreign Patent Office in a counterpart foreign application not more than three (3) months prior to the filing of this Information Disclosure Statement; or
			No item of information contained in this Information Disclosure Statement was cited in a communication from a foreign Patent Office in a counterpart foreign application, and, to the knowledge of the undersigned, after making reasonable inquiry, no item of information contained in the Information Disclosure Statement was known to any individual designated in 37 C.F.R. 1.56(c) more than three (3) months prior to the filing of this Information Disclosure Statement.
Statement Under 37 C.F.R. 1.704 (d) - (Patent Term Adjustment): (Applies to original applications, other than designs, filed on or after May 29, 2000)			
1	[)	Each item of information contained in the Information Disclosure Statement was cited in a communication from a foreign Patent Office in a counterpart application and this communication was not received by any individual designated in §1.56(c) more than thirty (30) days prior to the filing of the Information Disclosure Statement.
Enclosed Herewith is Form PTO-1449, and:			
	[XX]	[]	Copies of the cited references are enclosed.
]		prior application, U.S. Serial No, to which priority under 35 U.S.C. 120 is claimed (The earlier application contains copies of the cited references).
•	[]	The listed references were cited in the enclosed International Search Report in a counterpart foreign application.
	[}	The "concise explanation" requirement (non-English reference) for Reference(s) under 37 C.F.R. 1.98(a)(3) is satisfied by:
			 [] the explanation provided on the attached sheet; [] the explanation provided in the specification; [] submission of the enclosed International Search Report; or [] the enclosed English language Abstract.
	[]	Applicant requests that the following pending applications be

U.S. Patent/Application No. ______, filed/issued _
U.S. Patent/Application No. _____, filed/issued _
U.S. Patent/Application No. _____, filed/issued _____,

Date

considered:

Examiner

[] A copy of each above-cited application, including the current claims, is enclosed.

A copy of each above-cited application, including the current claims, is enclosed, except those entered in prior application Serial No._______, to which priority under 35 U.S.C. 120 is claimed.

The Examiner is respectfully requested to return a copy of the above list of pending applications indicating which references were considered with the next Official Action.

Further, it is respectfully requested that the information disclosed herein be made of record in this application.

Method of Payment:

- [] A check for the fee noted above is enclosed.
- [] Please charge our deposit account No. 14-1431.
- [XX] The Commissioner is authorized to charge any deficiency in payment of fees and credit any overpayment to our Deposit Account No. 14-1431.

Respectfully submitted,

Peter C. Michalos Reg. No. 28,643

Attorney for Applicant(s)

(212) 564-0200

Dated: March 5, 2002

NOTARO & MICHALOS P.C. Empire State Building 350 Fifth Avenue, Suite 6902 New York, NY 10118-6985

Examiner:

Sheet 0/202,996 Serial H60-104 US FORM PTO-1449 Atty. Docket Number: Number: LIST OF PRIOR ART CITED BY Applicant: J. Ramm APPLICANT Filing Date: 10/25/01 Group: U.S. PATENT DOCUMENTS Sub-Filing Class Document Number Date Name EI* class Date 11/15/77 Suntola et al. 156 611 11/25/75 4 0 5 3 AA 275 12/11/81 7 06/28/83 Suntola et al. 118 AΒ 4 3 8 9 9 3 427 255.2 06/21/79 Suntola et al. 2 11/01/83 AC 4 4 1 3 0 2 7 7 0 12/10/91 Kelly 427 38 06/11/90 5 1 6 AD 0 92 06/29/99 Sherman 117 08/16/96 ΑE 5 9 1 6 3 6 5 255.3 11/26/97 9 7 2 4 3 10/26/99 DiMeo, Jr. et al. 427 AF 427 255.2 11/28/95 1 5 5 9 01/18/00 Suntola et al. 6 0 ΑG AΗ ΑI ΑJ ΑK FOREIGN PATENT DOCUMENTS Sub-Translated Class Country Document Number Date class Y Ν AL AM ΑN ΑO Other Prior Art (incl. Author, Title, Date, Pertinent Pages, etc.) Hiramatsu, K, et al!, "Formation of TiN films with low CI concentration by AR pulsed plasma chemical vapor deposition", <u>J. Vac. Sci. Technol.</u> A 14(3) May/Jun 1996, 1037-1040. Rossnagel, S.M., "Plasma-enhanced atomic layer deposition of Ta and Ti for AS interconnect diffusion barriers", J. Vac. Sci. Technol. B 18(4), Jul/Aug 2000, 2016-2020. AΤ Swiss Search Report, dated July 27, 2001.

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with N Draw line through citation if not in conformance and not considered. Include copy of this f next communication to applicant.

Date Considered: